

**REMARKS**

At the outset, the Examiner is thanked for the thorough review and consideration of the subject application. The Final Office Action of October 22, 2002 has been received and contents carefully reviewed.

Claims 1-20 are pending in this application. Reexamination and reconsideration are respectfully requested.

The Examiner rejected claims 1, 2, 4-6, and 8-20 under 35 U.S.C. § 102(e) as being anticipated by Kim et al. (U.S. Patent No. 6,038,008); and rejected claims 1, 2, 4-6, and 8-20 under the judicially created doctrine of obviousness-type double patenting as being unpatentable over claims 1-10 and 15-17 of U.S. Patent No. 6,038,008. Applicants respectfully traverse these rejections.

Claim 1 is allowable at least for the reason that claim 1 recites a combination of elements including irradiating the organic passivation layer with ultraviolet rays to form a hydrophilic buffer layer. Claim 9 is allowable at least for the reason that claim 9 recites a combination of elements including a buffer layer over said passivation layer.

None of the cited references, singly or in combination, teaches or suggests at least these features.

In Kim et al., the surface of the organic protection layer is treated by sputter etching, dry etching, or ultra-violet (UV) radiation treatment to produce a rough (or irregular) surface profile. The roughened surface of the protection layer increases adhesion to an ITO layer. Column 7.

In contrast, the present application teaches irradiating the surface of a passivation layer having a hydrophobic property with UV rays having wavelengths of about 100 to 200nm at a normal (atmospheric) pressure to form a buffer layer, beneficially of SiO<sub>2</sub> or of another oxide. The buffer layer has a hydrophilic property. The specification of this application discusses how

the contact angle on the surface of the buffer layer is made smaller after irradiation and that the adhesion is better between the transparent conductive material and its receiving surface. Further, Applicants respectfully submit that “hydrophilic” and “roughened” have different meanings.

Kim et al. may teach roughening to increase adhesion, however, the reference does not teach irradiating the organic passivation layer with ultraviolet rays to form a hydrophilic buffer layer as in claim 1 nor a buffer layer over said passivation layer as in claim 9.

As to the double-patent rejection, Applicants respectfully submit the claims (emphasis added) are not obvious over Kim et al. because they differ in scope from the claims of this patent. Nowhere in the claims of Kim et al. are the features of claims 1 and 9 taught or suggested. Applicants respectfully submit that the double patenting rejection should be withdrawn with respect to this application since these claims are drawn to a different invention and are patentably distinct.

Moreover, claims 2-8, and 10-20 are believed to be allowable by virtue of their dependence on claims 1 and 9, which are believed to be allowable.

The Examiner objected to claims 3 and 7 as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

In view of the above, each of the presently pending claims in this application is believed to be in immediate condition for allowance. Accordingly, the Examiner is respectfully requested to withdraw the outstanding rejection of the claims and to pass this application to issue.

Should the Examiner deem that a telephone conference would further the prosecution of this application, the Examiner is invited to call the undersigned attorney at (202) 496-7371. All correspondence should be sent to the address listed below.

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If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. § 1.136. Please credit any overpayment to deposit Account No. 50-0911.

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Respectfully submitted,  
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